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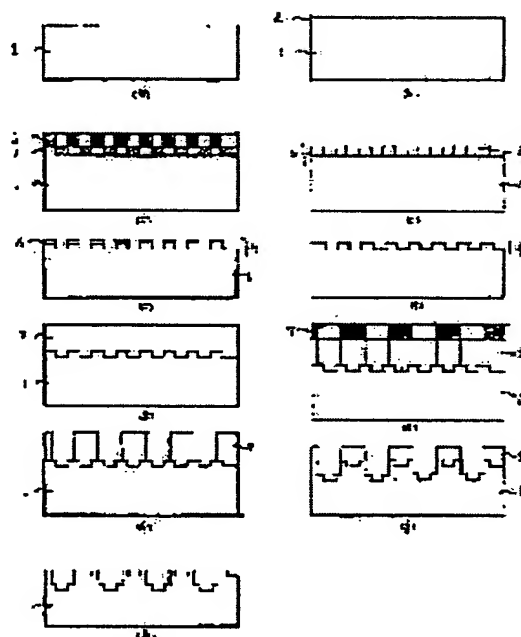
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(54) PRODUCTION OF GUIDE GROOVE WITH MARKER

(57)Abstract:

PURPOSE: To limit a transfer rate by producing guide grooves added with markers at the groove bottoms in order to prevent the defect at the time of parting of a stamper and a disk in injection molding of a magneto-optical disk.

CONSTITUTION: This process for production of the guide grooves with markers comprises producing the guide grooves with markers on a master plate 1 on the inner side of its use region and forming the guide grooves with markers by executing application of a first photosensitive body, contact exposing and etching for the purpose of forming the markers, then executing applying of a second photosensitive body, contact exposing and etching for the purpose of producing the guide grooves. The guide grooves with markers are maintained at the transfer rate of the specified quantity by measuring the guide groove, by which the defect generated at the time of parting the stamper and the disk is prevented and the molded articles having higher accuracy are produced.



CLAIMS

[Claim(s)]

[Claim 1] In the guide rail production approach with a marker which produces a guide rail with a marker inside an instructions slot field in case master original recording is produced The process which washes quartz original recording, and the process which applies a photo conductor to the washed quartz original recording, The process which carries out adhesion exposure of the detailed pattern at the applied photo conductor, and the development process which forms a detailed pattern by development after exposure, The process etched into the predetermined depth by using a detailed pattern as a mask, and the process which ashes and removes a resist after etching, It is the production approach of having the last washing process. The 1st photo conductor spreading for marker production, The 1st adhesion exposure, the 1st etching process for forming the predetermined marker depth, and the marker of a predetermined configuration are produced. A production of a guide rail pattern predetermined after that sake, The guide rail production approach with a marker characterized by having the 2nd photo conductor spreading, the 2nd adhesion exposure, and the 2nd etching process.

[Claim 2] The guide rail production approach with a marker characterized by producing a marker first and producing a predetermined guide rail pattern after that in the guide rail production approach with a marker according to claim 1.